

Answer to tutorial questions – 01

ME4252 Nanomaterial for Energy Engineering

1. Determine the temperature at which an energy level which is 0.3 eV below Fermi energy is 2% unoccupied by an electron.

Answer:

$$0.98 = \frac{1}{1 + \exp\left(-\frac{0.3}{8.25 \times 10^{-5} \times T}\right)}$$
$$\Rightarrow T = 894 \text{ K}$$

2. The value of  $p_0$  in Si at  $T = 300 \text{ K}$  is  $10^{15} \text{ cm}^{-3}$ . Determine the following:
  - (i) The position of Fermi energy below conduction band edge, and
  - (ii) Equilibrium concentration of electrons

Note that for Si at  $300 \text{ K}$ ,  $N_v = 1.04 \times 10^{19} \text{ cm}^{-3}$  and  $N_c = 2.8 \times 10^{19} \text{ cm}^{-3}$ .

Assume  $E_g$  of Si is  $1.12 \text{ eV}$ .

Solution:

Given,  $p_0 = 10^{15} \text{ cm}^{-3}$  and for Si,  $N_v = 1.04 \times 10^{19} \text{ cm}^{-3}$

i. And we know  $p_0 = N_v \exp\left(-\frac{E_F - E_v}{kT}\right)$

$$10^{15} = 1.04 \times 10^{19} \exp\left(-\frac{E_F - E_v}{0.0259}\right)$$

$$\Rightarrow E_F - E_v = 0.24 \text{ eV}$$

$$\text{Given, } E_g = 1.12 \text{ eV}$$

$$\Rightarrow E_c - E_F = 0.88 \text{ eV}$$

$$\text{Using, } E_c - E_F = 0.88 \text{ eV in } n_0 = N_c \exp\left(-\frac{E_c - E_F}{kT}\right)$$

$$\text{We get, } n_0 = 4.91 \times 10^4 \text{ cm}^{-3}$$

3. A semiconductor has  $N_C = 10^{19} \text{ cm}^{-3}$ ,  $N_v = 5 \times 10^{18} \text{ cm}^{-3}$  and  $E_g = 2 \text{ eV}$  doped with  $10^{17} \text{ cm}^{-3}$  donors (fully ionized)
- Calculate the intrinsic, electron and hole concentrations at  $627^\circ\text{C}$
  - Where is  $E_F$  located relative to  $E_i$ ?
  - Sketch the simplified band diagram, showing the position of  $E_F$  (assume the  $E_i$  is nearly at the midgap).

Answer:

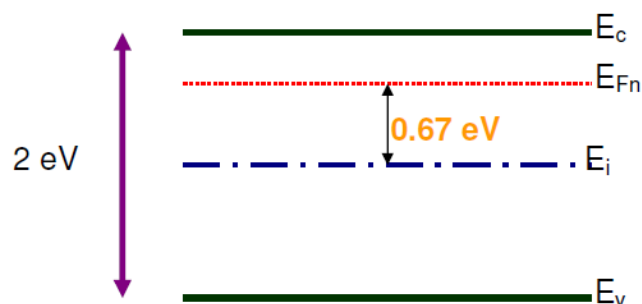
- (a) Intrinsic carrier concentration at  $627^\circ\text{C}$ ,  $n_i = 1.77 \times 10^{13} \text{ cm}^{-3}$

Electron concentration,  $n \sim N_D = 10^{17} \text{ cm}^{-3}$

Hole concentration,  $p = 3.15 \times 10^9 \text{ cm}^{-3}$

- (b)  $E_F - E_i = 0.67 \text{ eV}$

(c)



4. The Ge is now doped with Boron and with Phosphorous. Both dopants have the same concentration. Assume the Boron and Phosphorous energy levels are each 40 meV from the band edge. If  $m_n^*/m_p^* = 0.01$ , draw the band diagram of the doped Ge as accurately as you can, showing  $E_g$ ,  $E_f$  and  $E_i$ . Assume  $E_g$  of Ge is 0.67eV.

Answer:

$$E_i = \text{midgap} + 89\text{meV}$$

5. Consider a GaAs semiconductor illuminated with photons of energy 1.65 eV. The absorption coefficient at 1.65 eV is  $10^4 \text{ cm}^{-1}$ .
- (a) Determine the thickness of the material so that 75% of the energy is absorbed.
- (b) Determine the thickness so that 75% of the energy is transmitted.

Given: At  $h\nu = 1.65 \text{ eV}$ ,  $\alpha = 10^4 \text{ cm}^{-1}$ .

Answer:

- (a)  $t = 1.39\mu\text{m}$
- (b)  $t = 0.29\mu\text{m}$

6. The optical properties of silicon measured at 300K are given below:

Wavelength ( nm)	Absorption coefficient ( $\text{cm}^{-1}$ )	Refraction coefficient R
400	$1 \times 10^4$	0.49
700	$1.90 \times 10^3$	0.34

Two monochromatic light sources at 400 nm and 700 nm are available to illuminate a silicon solar cell of 1  $\mu\text{m}$  thick. Recommend the most suitable source for illumination.

Assume that the light incidents normally on the front surface of the solar cell with an intensity of  $10 \text{ W/cm}^2$ .

Answer:

$$\text{At } 400\text{nm}, R = 0.49$$

$$I(a) = 3.2\text{W/cm}^2$$

$$\text{At } 700\text{nm}, R = 0.34$$

$$I(a) = 1.1\text{W/cm}^2$$

Based on the intensity of absorbed light calculated above, the most suitable source for illumination is: monochromatic light source at  $400 \text{ nm}$ .